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3681

PATENT
30205/37456

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Lee et al.

Serial No.: 09/884,313

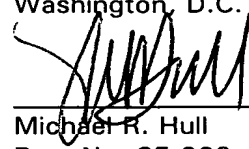
Filed: June 19, 2001

For: Photoresist Polymer for Top-Surface Imaging Process by Silylation and Photoresist Composition Containing the Same

Group Art Unit: 3681

Examiner: To be assigned

) I hereby certify that this paper and
) the documents referred to as
) enclosed therewith are being
) deposited with the United States
) Postal Service as first class mail,
) postage prepaid, on **November 14,**
) **2001**, in an envelope addressed to
) Commissioner for Patents,
) Washington, D.C. 20231.

)  #5
) Michael R. Hull
) Reg. No. 35,902
) Attorney for Applicants
)

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, D.C. 20231

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Sir:

The patents and search report listed on the enclosed PTO Form-1449 are submitted pursuant to 37 CFR §§ 1.56, 1.97, and 1.98. Copies of the patents and search report are enclosed as necessary.

This information disclosure statement is being filed, to the best of the undersigned's knowledge, before the mailing date of a first Office Action on the merits. In accordance with 37 CFR §1.97(b), no certification or fee is required.

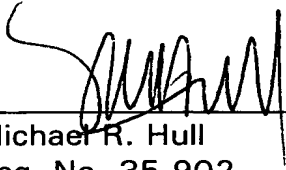
The Commissioner is authorized to charge any fee deficiency required by this paper, or credit any overpayment, to Deposit Account No. 13-2855. A copy of this paper is enclosed.

Respectfully submitted,

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November 14, 2001

By:



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